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Attorney Docket No.: PATENT
SSI-00700

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:)	Group Art Unit: 1763
Maximilian A. Biberger et al.)	Examiner: Ram N. Kacker
Serial No.: 09/704,641)	TRANSMITTAL LETTER
Filed: November 1, 2000)	162 North Wolfe Road
For: METHOD AND APPARATUS FOR)	Sunnyvale, California 94086
SUPERCritical PROCESSING)	(408) 530-9700
OF A WORKPIECE)	Customer Number 28960

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

Enclosed please find a request for consideration of information disclosure statements mailed March 16, 2001, October 30, 2002, October 1, 2003, and June 24, 2004 for filing with the U.S. Patent and Trademark Office. Also, attached are copies of the information disclosure statements as filed on the above dates.

The Commissioner is authorized to charge any additional fee or credit any overpayment to our Deposit Account No. 08-1275. **An originally executed duplicate of this transmittal is enclosed for this purpose.**

Respectfully submitted,
HAVERSTOCK & OWENS LLP

Dated: October 5, 2004

By: Thomas B. Haverstock
Thomas B. Haverstock
Reg. No.: 32,571

Attorneys for Applicants

CERTIFICATE OF MAILING (37 CFR § 1.8(a))

I hereby certify that this paper (along with any referred to as being attached or enclosed) is being deposited with the U.S. Postal Service on the date shown below with sufficient postage as first class mail in an envelope addressed to the: Commissioner for Patents, P.O. Box 1450 Alexandria, VA 22313-1450

HAVERSTOCK & OWENS LLP
Date: 10-5-04 By: [Signature]



PATENT
Attorney Docket No.: SSI-00700

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In re Application of:

Maximilian A. Biberger et al.

Serial No.: 09/704,641

Filed: November 1, 2000

For: **METHOD AND APPARATUS FOR
SUPERCritical PROCESSING
OF A WORKPIECE**

) Group Art Unit: 1763

) Examiner: Ram N. Kackar

) **REQUEST FOR CONSIDERATION OF
INFORMATION DISCLOSURE
STATEMENTS MAILED March 16, 2001,
October 30, 2002, and October 1, 2003, and
ELECTRONICALLY FILED June 24,
2004**

) 162 N. Wolfe Road
) Sunnyvale, CA 94086
) (408) 530-9700

) Customer No.: 28960

Commissioner for Patents
P.O. Box 1450
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Sir:

The Examiner has acknowledged all the information disclosure statements filed in this case except those (1) mailed on March 16, 2001, (2) mailed on October 30, 2002, (3) mailed on October 1, 2003, and (4) electronically filed on June 24, 2004 (EFS ID 63275). For the Examiner's convenience, the Applicants have enclosed a copy of (1) each of the mailed information disclosure statements with its accompanying Form PTO-1449 and stamped return postcard and (2) the Acknowledgment Receipt for the electronically filed IDS. The Applicants would greatly appreciate acknowledgment of these information disclosure statements by having the enclosed Forms PTO-1449 and the Acknowledgment Receipt initialed and returned.

Respectfully submitted,
HAVERSTOCK & OWENS LLP

Dated: 10-5-04

By: Thomas B. Haverstock
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Reg. No.: 32,571

Attorneys for Applicants

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For: **METHOD AND APPARATUS FOR
SUPERCritical PROCESSING
OF A WORKPIECE**

) Group Art Unit:

) Examiner:

) **TRANSMITTAL LETTER**

) 260 Sheridan Avenue, Suite 420
) Palo Alto, California 94306
) (650)833-0160

Assistant Commissioner for Patents
Washington, D.C. 20231

Sir:

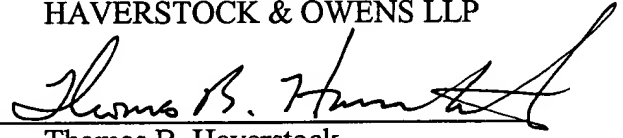
Enclosed please find an Information Disclosure Statement, and Form PTO-1449, including copies of the references contained thereon, for filing in the U.S. Patent and Trademark Office.

The Commissioner is hereby authorized to charge any additional fee or credit overpayment to our Deposit Account No. 08-1275. **An originally executed duplicate of this transmittal is enclosed for this purpose.**

Respectfully submitted,
HAVERSTOCK & OWENS LLP

Dated: 3-14-01

By:


Thomas B. Haverstock
Reg. No.: 32,571
Attorneys for Applicants

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HAVERSTOCK & OWENS LLP


3/14/01



COPY

Serial No.: 09/704,641 H&O File No.: SSI-00700 By: TBH/JR
In the Matter of The Application of: Maximilian A. Biberger et al.
Date Mailed: 3/16/01 Due Date:

The following has been received in the U.S. Patent and Trademark Office on the date stamped hereon:

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) **STATEMENT**

) 260 Sheridan Avenue, Suite 420
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Assistant Commissioner for Patents
Washington, D.C. 20231

Sir:

The citations listed below, copies attached, may be material to the examination of the above-identified application, and are therefore submitted in compliance with the duty of disclosure defined in 37 C.F.R. §§ 1.56 and 1.97. The Examiner is requested to make these citations of official record in this application.

Applicants have become aware of the following printed publications which may be material to the examination of this application:

- U.S. Patent No. 2,617,719;
- U.S. Patent No. 3,890,176;
- U.S. Patent No. 3,900,551;
- U.S. Patent No. 4,029,517;
- U.S. Patent No. 4,091,643;
- U.S. Patent No. 4,341,592;
- U.S. Patent No. 4,474,199;
- U.S. Patent No. 4,475,993;
- U.S. Patent No. 4,601,181;
- U.S. Patent No. 4,693,777;
- U.S. Patent No. 4,749,440;
- U.S. Patent No. 4,788,043;

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HAVERSTOCK & OWENS LLP.
Date: 3/16/01 By: [Signature]

- U.S. Patent No. 4,838,476;
- U.S. Patent No. 4,865,061;
- U.S. Patent No. 4,879,004;
- U.S. Patent No. 4,923,828;
- U.S. Patent No. 4,924,892;
- U.S. Patent No. 4,944,837;
- U.S. Patent No. 4,960,140;
- U.S. Patent No. 4,983,223;
- U.S. Patent No. 5,011,542;
- U.S. Patent No. 5,013,366;
- U.S. Patent No. 5,068,040;
- U.S. Patent No. 5,105,556;
- U.S. Patent No. 5,143,103;
- U.S. Patent No. 5,158,704;
- U.S. Patent No. 5,174,917;
- U.S. Patent No. 5,185,058;
- U.S. Patent No. 5,185,296;
- U.S. Patent No. 5,193,560;
- U.S. Patent No. 5,213,619;
- U.S. Patent No. 5,215,592;
- U.S. Patent No. 5,225,173;
- U.S. Patent No. 5,236,602;
- U.S. Patent No. 5,237,824;
- U.S. Patent No. 5,261,965;
- U.S. Patent No. 5,266,205;
- U.S. Patent No. 5,267,455;
- U.S. Patent No. 5,274,129;
- U.S. Patent No. 5,288,333;
- U.S. Patent No. 5,290,361;
- U.S. Patent No. 5,294,261;
- U.S. Patent No. 5,304,515;
- U.S. Patent No. 5,306,350;
- U.S. Patent No. 5,313,965;

- U.S. Patent No. 5,316,591;
- U.S. Patent No. 5,334,332;
- U.S. Patent No. 5,334,493;
- U.S. Patent No. 5,337,446;
- U.S. Patent No. 5,352,327;
- U.S. Patent No. 5,355,901;
- U.S. Patent No. 5,356,538;
- U.S. Patent No. 5,368,171;
- U.S. Patent No. 5,370,740;
- U.S. Patent No. 5,377,705;
- U.S. Patent No. 5,401,322;
- U.S. Patent No. 5,403,621;
- U.S. Patent No. 5,417,768;
- U.S. Patent No. 5,456,759;
- U.S. Patent No. 5,470,393;
- U.S. Patent No. 5,482,564;
- U.S. Patent No. 5,494,526;
- U.S. Patent No. 5,500,081;
- U.S. Patent No. 5,501,761;
- U.S. Patent No. 5,514,220;
- U.S. Patent No. 5,522,938;
- U.S. Patent No. 5,526,834;
- U.S. Patent No. 5,533,538;
- U.S. Patent No. 5,547,774;
- U.S. Patent No. 5,550,211;
- U.S. Patent No. 5,580,846;
- U.S. Patent No. 5,589,105;
- U.S. Patent No. 5,632,847;
- U.S. Patent No. 5,635,463;
- U.S. Patent No. 5,637,151;
- U.S. Patent No. 5,641,887;
- U.S. Patent No. 5,656,097;
- U.S. Patent No. 5,665,527;

- U.S. Patent No. 5,679,169;
- U.S. Patent No. 5,679,171;
- U.S. Patent No. 5,683,977;
- U.S. Patent No. 5,688,879;
- U.S. Patent No. 5,700,379;
- U.S. Patent No. 5,726,211;
- U.S. Patent No. 5,739,223;
- U.S. Patent No. 5,783,082;
- U.S. Patent No. 5,798,438;
- U.S. Patent No. 5,804,607;
- U.S. Patent No. 5,868,856;
- U.S. Patent No. 5,868,862;
- U.S. Patent No. 5,872,257;
- U.S. Patent No. 5,873,948;
- U.S. Patent No. 5,881,577;
- U.S. Patent No. 5,908,510;
- U.S. Patent No. 5,944,996;
- U.S. Patent No. 5,976,264;
- U.S. Patent No. 5,980,648;
- U.S. Patent No. 6,017,820;
- U.S. Patent No. 6,024,801;
- European Publication No. EP 0 726 099 A2;
- European Publication No. EP 0 587 168 A1;
- European Publication No. EP 0 572 913 A1;
- European Publication No. EP 0 536 752 A2;
- European Publication No. EP 0 283 740 A2;
- European Publication No. EP 0 302 345 A2;
- European Publication No. EP 0 370 233 A1;
- European Publication No. EP 0 391 395;
- Japanese Patent Abstract JP 2-304941;
- Japanese Patent Abstract JP 727711;
- Japanese Patent Abstract JP 1045131;
- Japanese Patent Abstract JP 2-148841;

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- Japanese Patent Abstract JP 8222508;
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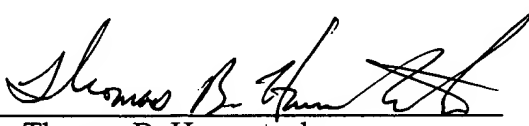
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- Tolley, W.K. et al., "Stripping organics from metal and mineral surfaces using supercritical fluids," Separation Science and Technology, Vol. 22, pp 1087-1101, 1987; and
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Attorney Docket No.: PATENT
SSI-00700

This Information Disclosure Statement under 37 C.F.R. §§ 1.56 and 1.97 is not to be construed as a representation that a search has been made, that additional information material to the examination of this application does not exist, or that anyone or more of these citations constitutes prior art.

Respectfully submitted,
HAVERSTOCK & OWENS LLP

Dated: 3-14-01

By: 
Thomas B. Haverstock
Reg. No.: 32,571

Attorneys for Applicants

FORM PTO-1449 Commerce (Modified)		U.S. Department of Patent and Trademark Office		Attorney Docket No.: SSI-00700		Serial No.: 09/704,641	
INFORMATION DISCLOSURE STATEMENT BY APPLICANT (Use Several Sheets If Necessary)				Applicant: Maximilian A. Biberger et al.			
(37 CFR § 1.98(b))				Filing Date: November 1, 2000		Group Art Unit:	

U.S. PATENT DOCUMENTS							
Examiner Initials	Serial / Patent Number	Issue Date	Applicant / Patentee	Class	Subclass	Filing Date	
	AA	2,617,719	Stewart	23	312	12/29/50	
	AB	3,890,176	Bolon	156	2	12/17/73	
	AC	3,900,551	Bardoncelli et al.	423	9	03/02/72	
	AD	4,029,517	Rand	134	11	03/01/76	
	AE	4,091,643	Zucchini	68	18	02/17/77	
	AF	4,341,592	Shories et al.	156	643	08/04/75	
	AG	4,474,199	Blaudszun	134	105	11/09/82	
	AH	4,475,993	Blander et al.	204	64T	08/15/83	
	AI	4,601,181	Privat	68	18	11/17/83	
	AJ	4,693,777	Hazano et al.	156	345	11/27/85	
	AK	4,749,440	Blackwood et al.	156	646	05/12/87	
	AL	4,788,043	Kagiyama et al.	422	292	04/17/86	
	AM	4,838,476	Rahn	228	180.1	11/12/87	
	AN	4,865,061	Fowler et al.	134	108	07/22/83	
	AO	4,879,004	Oesch et al.	203	89	05/04/88	
	AP	4,923,828	Gluck et al.	437	225	08/07/89	
	AQ	4,924,892	Kiba et al.	134	123	07/28/88	
	AR	4,944,837	Nishikawa et al.	156	646	02/28/89	
	AS	4,960,140	Ishijima et al.	134	31	11/27/85	
	AT	4,983,223	Gessner	134	25.4	10/24/89	
	AU	5,011,542	Weil	134	38	07/21/88	
	AV	5,013,366	Jackson et al.	134	1	12/07/88	
	AW	5,068,040	Jackson	210	748	04/03/89	
	AX	5,105,556	Kurokawa et al.	34	12	08/09/88	
	AY	5,143,103	Basso et al.	134	98.1	01/04/91	
	AZ	5,158,704	Fulton et al.	252	309	07/25/90	
	BA	5,174,917	Monzyk	252	60	07/19/91	
	BB	5,185,058	Cathey, Jr.	156	656	01/29/91	
	BC	5,185,296	Morita et al.	437	229	04/24/91	
	BD	5,193,560	Tanaka et al.	134	56R	06/24/91	
	BE	5,213,619	Jackson et al.	134	1	11/30/89	
	BF	5,215,592	Jackson	134	1	01/22/91	
	BG	5,225,173	Wai	423	2	10/25/91	
	BH	5,236,602	Jackson	210	748	01/28/91	
	BI	5,237,824	Pawliszyn	62	51.1	10/12/90	
	BJ	5,261,965	Moslehi	134	1	08/28/92	

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(37 CFR § 1.98(b))				Filing Date: November 1, 2000		Group Art Unit:	

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	BW	5,337,446	Smith et al.	15	21.1	10/27/92	
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	BY	5,355,901	Mielnik et al.	134	105	10/27/92	
	BZ	5,356,538	Wai et al.	210	634	10/21/91	
	CA	5,368,171	Jackson	134	147	07/20/92	
	CB	5,370,740	Chao et al.	134	1	10/01/93	
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	CD	5,401,322	Marshall	134	13	06/30/92	
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